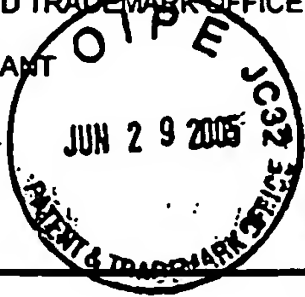


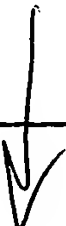




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U.S. PATENT DOCUMENTS							
Examiner's Initials	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	6,013,583	01/2000	Ajmera et al.			
	AB						
	AC						
	AD						
	AE						
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	AG						
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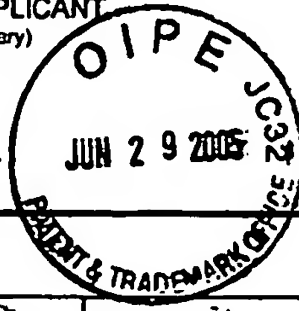
FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
057	0817251 A1	11.06.97	EPO (IBM)				
D~	US2004/021156	07.07.03	PCT (Micron - Internat'l Search Rep.)				
AL							


OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	AM		Chen et al., <i>Excimer Laser-Induced Ti Silicidation to Eliminate the Fine-Line Effect for Integrated Circuit Device Fabrication</i> , J. ELECTROCHEM. SOC., Vol. 149, No. 11, pp. G609-G612 (2002).
	AN		Nishiyama et al., <i>Agglomeration Resistant Self-Aligned Silicide Process Using N₂ Implantation Into TiSi₂</i> , JPN. J. APPL. PHYS., Vol. 36, Pt. 1, No. 6A, pp. 3639-3643 (June 1997).
	AO		Wolf, <i>Chapter 13: Polycides and Salicides of TiSix, CoSi2, and NiSi</i> , SILICON PROCESSING FOR THE VLSI ERA, Vol. IV, pp. 603-604 (pre-2003).

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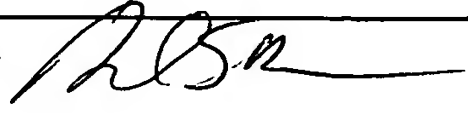
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U.S. PATENT DOCUMENTS							
Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	AA	2001/0041250 A1	11/2001	Werkhoven et al.			
	AB	2002/0000195 A1	01/2002	Bang et al.			
	AC	2002/0018849 A1	02/2002	George et al.			
	AD	2003/0032281 A1	02/2003	Werkhoven et al.			
	AE	2003/0129826 A1	07/2003	Werkhoven et al.			
	AF	2004/0209484 A1	10/2004	Hill et al.			
	AG	2004/0266153 A1	12/2004	Hu			
	AH						
	AI						

FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ							
	AK							
	AL							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)			
	AM		
	AN		
	AO		

EXAMINER	DATE CONSIDERED  7/19/05
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